



Spin Coater



Spin coating of polymers, nanomaterials, colloids and photoresists

By spinning at high speed a small drop of solution onto the center of a substrate, the fluid spreads to the edges by centrifugal force leaving a thin film. The thickness of the film depends on the concentration of the solution material, the type of solvent and the spinning speed.

It allows:

- To form uniform thin films over flat substrates for microfabrication processes
- Obtaining thicknesses of the order of microns to nanometers

Technical specifications

- Two spin coaters available (one dedicated to PDMS deposition).
- Rotational speed:
 - No PDMS spin coater: 100 to 12.000 rpm.
 - PDMS spin coater: from 100 to 6000 rpm.
- Vacuum chucks: 45 mm and 100 mm diameters. Designed to lock substrates firmly, without deflection, and operate at very high rotational speed.
- Fragment adapters: 3 mm to 10 mm; 5 mm to 25 mm; 10 mm to 50 mm.
- Holders with an O-ring seal to maintain the vacuum level and at the same time cushion the substrate.